

**RADIATION SENSITIVE SILICON-CONTAINING NEGATIVE RESISTS
AND USE THEREOF**

ABSTRACT OF THE DISCLOSURE

5 A negative resist composition, comprising:

 (a) silicon-containing polymer with pendant fused moieties selected from the group consisting of fused aliphatic moieties, homocyclic fused aromatic moieties, and heterocyclic fused aromatic and sites for reaction with a crosslinking agent,

 (b) an acid-sensitive crosslinking agent, and

10 (c) a radiation-sensitive acid generator is provided. The resist composition is used to form a patterned material layer in a substrate.